

L Number	Hits	Search Text	DB	Time stamp
157	181	(resist or photoresist) same (ash\$3 or stripp\$3) same bias	USPAT; EPO; JPO; IBM_TDB	2003/07/09 13:54
158	0	(resist or photoresist) same (ash\$3 or stripp\$3 remov\$3) same (partial\$@)	USPAT; EPO; JPO; IBM_TDB	2003/07/09 13:27
159	5244	(resist or photoresist) same (ash\$3 or stripp\$3 remov\$3) same (partial\$2)	USPAT; EPO; JPO; IBM_TDB	2003/07/09 13:29
160	5244	(resist or photoresist) same (ash\$3 or stripp\$3 or remov\$3) same (partial\$2)	USPAT; EPO; JPO; IBM_TDB	2003/07/09 13:29
161	49	(resist or photoresist) same (ash\$3 or stripp\$3 or remov\$3) same (partial\$2) same bias	USPAT; EPO; JPO; IBM_TDB	2003/07/09 13:30
162	5186	(resist or photoresist) and (ash\$3 or stripp\$3) and (bias or RF)	USPAT; EPO; JPO; IBM_TDB	2003/07/09 13:39
163	2085	(resist or photoresist) and (ash\$3 or stripp\$3) and (bias or RF) and (fence oe fencing)	USPAT; EPO; JPO; IBM_TDB	2003/07/09 13:40
164	60	(resist or photoresist) and (ash\$3 or stripp\$3) and (bias or RF) and (fence or fencing)	USPAT; EPO; JPO; IBM_TDB	2003/07/09 13:40
165	3529	(resist or photoresist) and (ash\$3 or stripp\$3) and bias	USPAT; EPO; JPO; IBM_TDB	2003/07/09 14:42
166	4457	(resist or photoresist or mask\$3) and (ash\$3 or stripp\$3) and bias	USPAT; EPO; JPO; IBM_TDB	2003/07/09 14:43
167	204	(resist or photoresist or mask\$3) same (ash\$3 or stripp\$3) same bias	USPAT; EPO; JPO; IBM_TDB	2003/07/09 15:03
168	1		USPAT	2003/07/09 14:55
169	1	(resist or photoresist or mask\$3) same patial\$3 same (remov\$3 or stripp\$3 or ash\$3)	USPAT; EPO; JPO; IBM_TDB	2003/07/09 15:04
170	8572	(resist or photoresist or mask\$3) same partial\$3 same (remov\$3 or stripp\$3 or ash\$3)	USPAT; EPO; JPO; IBM_TDB	2003/07/09 15:31
171	3229	(resist or photoresist or mask\$3) with partial\$3 with (remov\$3 or stripp\$3 or ash\$3)	USPAT; EPO; JPO; IBM_TDB	2003/07/09 15:05
172	14	((resist or photoresist or mask\$3) with partial\$3 with (remov\$3 or stripp\$3 or ash\$3)) same bias	USPAT; EPO; JPO; IBM_TDB	2003/07/09 15:06
173	263	(resist or photoresist or mask\$3) with (remov\$3 or stripp\$3 or ash\$3) with bias	USPAT; EPO; JPO; IBM_TDB	2003/07/09 15:32